



OMB No. 0651-0011

INFORMATION DISCLOSURE CITATION
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Atty. & Trademark No.
01222.0034-00000Serial No.
08/544,212Applicant
David A. RUSSO et al.Filing Date
October 17, 1995Group
Unknown

U.S. PATENT DOCUMENTS

*Examiner Initial	Document Number	Date	Name	Class	Sub Class	Filing Date If Appropriate
MM	RE 31,708	10/16/84	Gordon			
	2,617,741	11/11/52	Lytle			
	3,378,396	04/16/68	Zaromb			
	3,410,710	11/12/68	Mochel			
	3,460,960	08/12/69	Francel et al.			
	3,674,453	07/04/72	Loukes et al.			
	3,681,042	08/01/72	Edwards et al.			
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	3,710,074	01/09/73	Stewart			
	3,846,152	11/05/74	Franz			
	3,885,855	05/27/75	Gross			
	3,889,026	06/10/75	Groth			
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	3,934,587	01/27/76	Gordon			
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	3,984,581	10/05/76	Dobler et al.			
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	4,146,657	03/27/79	Gordon			
	4,187,336	02/05/80	Gordon			
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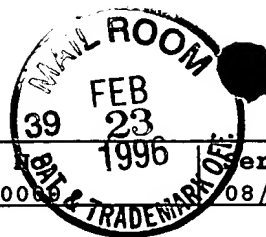
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Date Considered

6/2/96

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Atty. Docket 01222.0034-0006 Serial No. 08/544,212
Applicant David A. RUSSO et al.
Filing Date October 17, 1995 Group Unknown

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AM	4,585,674	04/29/86	Gordon			
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						Yes	No
AM	58-189263	04/28/82	Japan			X	
	57-34164	08/06/80	Japan			X	
	833649	02/12/79	USSR			X	
	84/02128	06/07/84	PCT			X	
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AM	Hochberg et al., "User's Guide for Glass Deposition with LTO-410™ Source Material", J.C. Schumacher & Co. (1990)✓
	S.B. Desu, "Decomposition Chemistry of Tetramethoxysilane" (1987)
	S.K. Raju et al., "Analytical Model for the Low Pressure Chemical Vapor Deposition of SiO ₂ from Tetraethoxysilane" ✗p
	Hochberg et al., "The Use of Liquid Sources in CVD Applications: Fire Safety Considerations and Delivery Methods" (1988)✗
	Williams et al., J. Electrochem. Soc. 134(3) 657-64 (1987)✓
AM	Hochberg et al., J. Electrochem. Soc. 136(6) 1843 (1989)✓

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6/28/96

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Sheet 1 of 2Form PTO-1449
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ATTY. DOCKET NO.

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SERIAL NO.

08/544,212

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(Use several sheets if necessary)

APPLICANT

David A. Russo, et al.

FILING DATE

October 17, 1995

GROUP

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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
AMY	3 3 7 8 3 9 6	4/16/68	Zaromb	—	—	
	3 9 4 9 1 4 6	4/6/76	Kane et al. ✓	—	—	
	4 1 8 7 3 3 6	2/5/80	Gordon	—	—	
	4 2 0 6 2 5 2	6/3/80	Gordon	—	—	
	4 3 0 8 3 1 6	12/29/8	Gordon	—	—	
	4 3 2 9 3 7 9	5/11/82	Terneu et al. ✓	—	—	
	4 3 8 6 1 1 7	5/31/83	Gordon	—	—	
	4 4 7 6 1 5 8	10/9/84	Baumberger et al. ✓	—	—	
	4 5 9 0 0 9 6	5/20/86	Lindner	—	—	
	4 6 0 1 9 1 7	7/22/86	Russo et al. ✓	—	—	
MM	4 6 9 6 8 3 7	9/29/87	Lindner	—	—	

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO

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J. Electrochem. Soc., Vol. 136, No. 6, (June 1989); "The LPCVD of Silicon Oxide
Films below 400°C from Liquid Sources"; A.K. Hockberg and D.L. O'Meara; Pages
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